

In the Claims

Claims 8 and 9 have been canceled, new claim 26 has been added, and claim 1 has been amended as follows:

1 1. (Currently amended) A method for removing contaminate particulate matter
2 from a contaminate particle containing substrate surface comprising the steps of:
3 applying a sacrificial coating of a material to a substrate surface containing
4 undesirable particulate matter thereon, which material is to encapsulate and
5 suspend the undesirable particles therein;
6 fluidizing the material if necessary;
7 applying energy to the coated substrate to dislodge at least some of the
8 particulate matter from the surface of the substrate into the fluid sacrificial
9 coating such that the particulate matter is partially or fully encapsulated and
10 suspended within the sacrificial coating forming a particulate matter
11 containing sacrificial material coating; and
12 forming the fluidized particulate matter containing sacrificial material coating
13 into a strippable film; and
14 removing the particulate matter containing sacrificial material coating
15 strippable film from the substrate surface providing a substrate surface
16 having less particulate matter thereon.

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1 2. (original) The method of claim 1 wherein the substrate is a semiconductor
2 wafer.

1 3. (original) The method of claim 1 wherein the sacrificial coating material is
2 a fluid.

1 4. (original) The method of claim 1 wherein the energy used is sonic energy.

1 5. (original) The method of claim 1 wherein the energy used is thermal,
2 centrifugal, magnetic or vibrational.

1 6. (original) The method of claim 1 wherein the sacrificial coating material is
2 a liquid.

1 7. (original) The method of claim 1 wherein the sacrificial coating material is
2 a curable polymer.

1 8.-9. (canceled)

1 10. (original) The method of claim 1 wherein the material is a gas, liquid,
2 vapor or fluid polymer.

1 11.-25. (Withdrawn)

1 26. (New) The method of claim 1 wherein the strippable film is formed
2 simultaneously with application of the energy to dislodge the particles.
